

IN THE SPECIFICATION

Please add the following beginning at page 6, line 22.

A1 In one embodiment, a nitride liner layer is formed on the CVD material layer in the CVD apparatus to a thickness of approximately 30\AA to 100\AA . A trench filling layer is then formed on the nitride liner layer in the CVD apparatus to a thickness of approximately 3000\AA to 10000\AA .

Please add the following begining at page 7, line 23 of the specification.

A2 Fig. 15 is a graph showing the effects of the present invention.